HUANG 3-8-3-2-2-25-5

A Mask Layer and Inte: Nect Structure for Dual Damascene Fabricati of a Semiconductor Device Robert L. Wolter (407-926-7700)
Serial #10/026,257

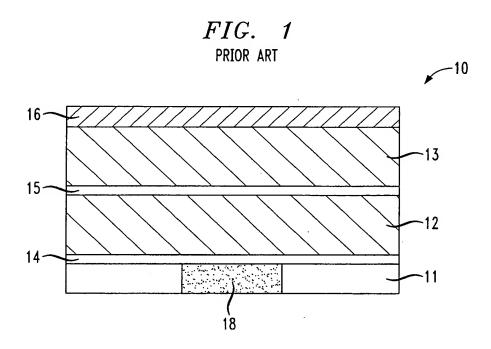
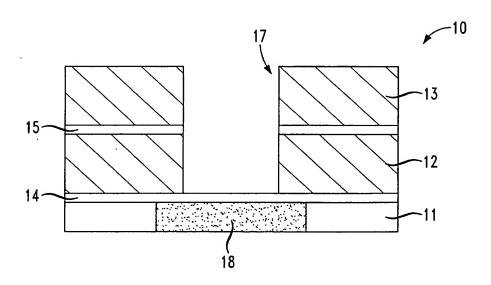


FIG.~2 PRIOR ART



HUANG 3-8-3-2-2-25-5

nect Structure for Dual Damascene Fabricati. A Mask Layer and Inte. of a Semiconductor Device Robert L. Wolter (407-926-7700) Serial #10/026,257

FIG. 3 PRIOR ART

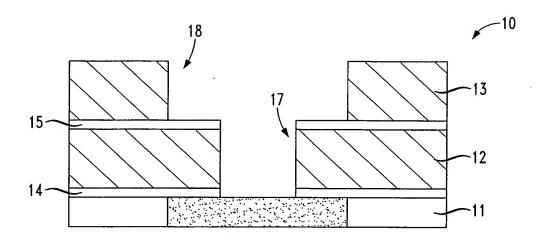
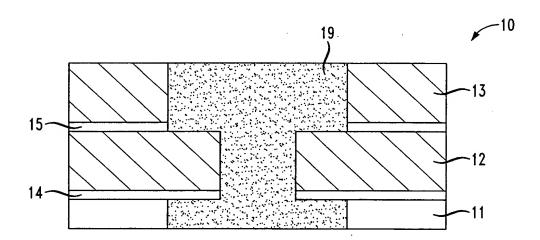


FIG. 4 PRIOR ART



HUANG 3-8-3-2-2-25-5
A Mask Layer and Inter sect Structure for Dual Damascene Fa

ect Structure for Dual Damascene Fabricatio of a Semiconductor Device Robert L. Wolter (407-926-7700) Serial #10/026,257

FIG.~5 PRIOR ART

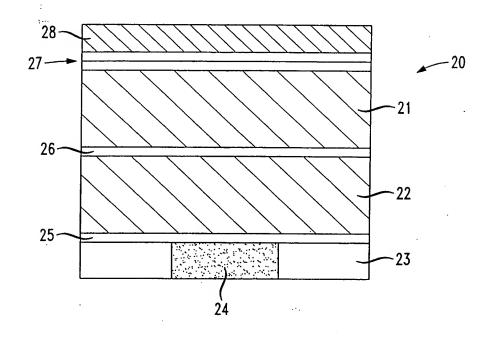
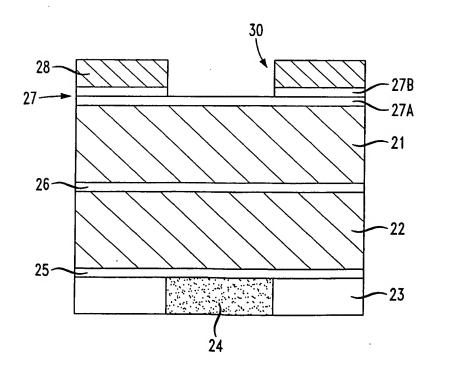


FIG. 6



HUANG 3-8-3-2-2-25-5 A Mask Layer and Intermeet Structure for Dual Damascene Fa

Robert L. Wolter (407-926-7700)
Serial #10/026,257

FIG. 7 PRIOR ART

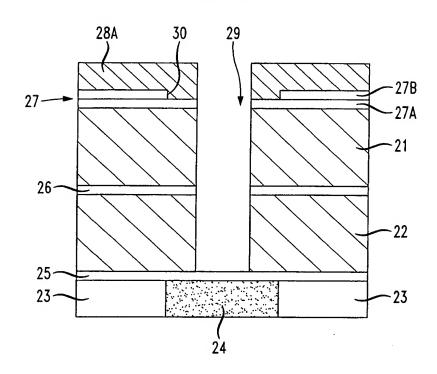
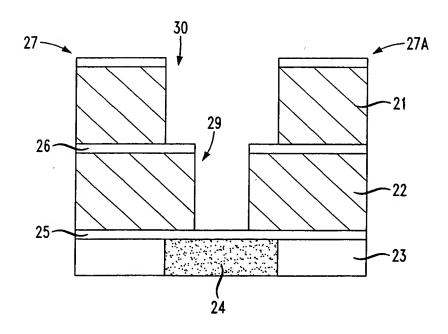


FIG. 8 PRIOR ART



HUANG 3-8-3-2-2-5-5

A Mask Layer and Inter. .ect Structure for Dual Damascene Fabricatio. i a Semiconductor Device Robert L. Wolter (407-926-7700)

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FIG. 9

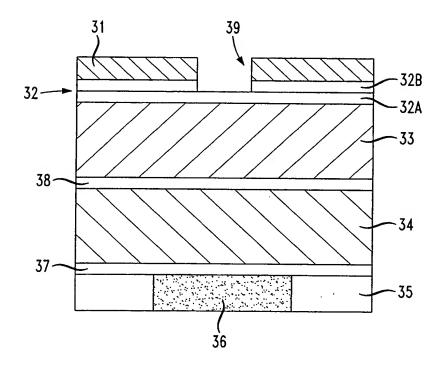


FIG. 10 PRIOR ART

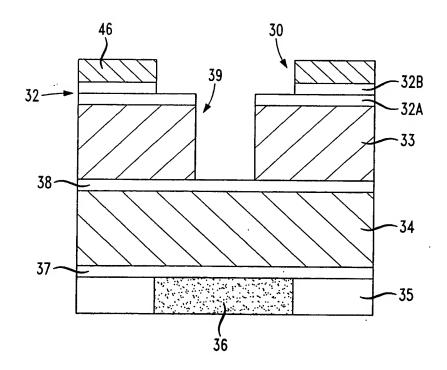


FIG. 11 PRIOR ART

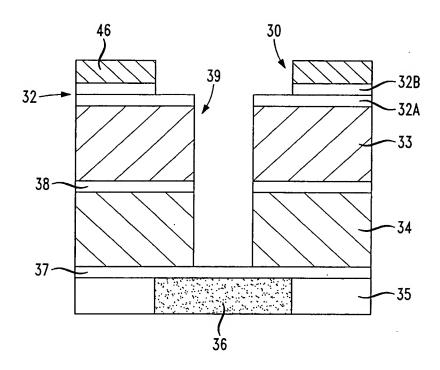
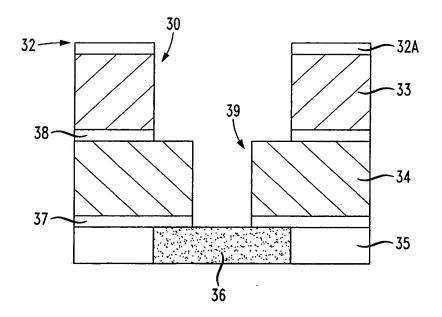


FIG. 12 PRIOR ART



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FIG. 13

PRIOR ART

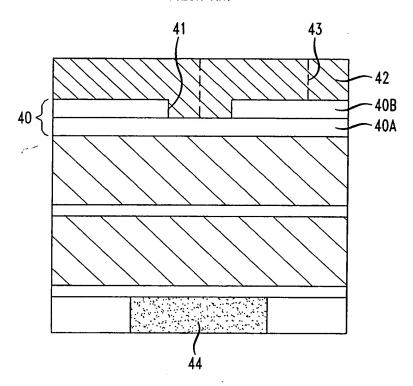


FIG. 14 PRIOR ART

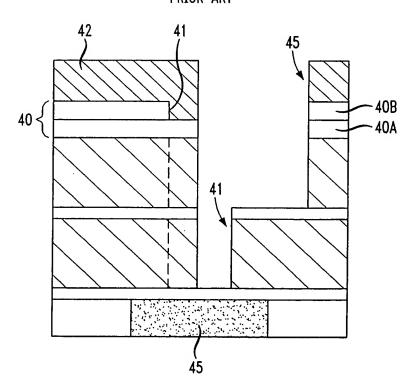


FIG. 15

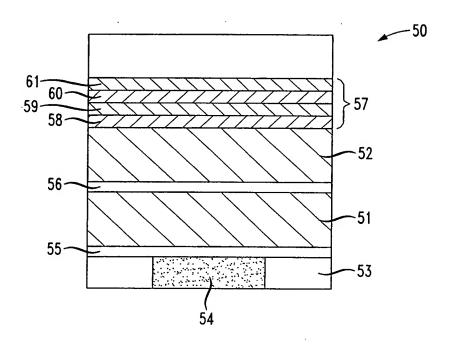
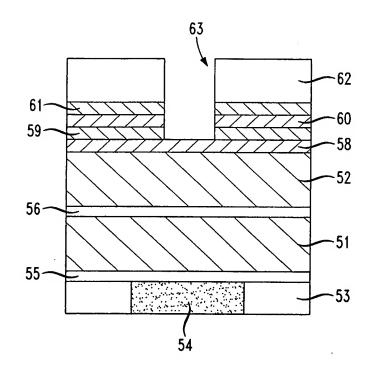


FIG. 16



Robert L. Wolter (407-926-7700) Serial #10/026,257

FIG. 17

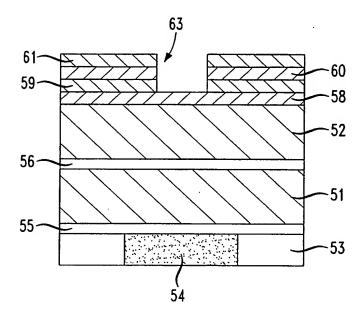
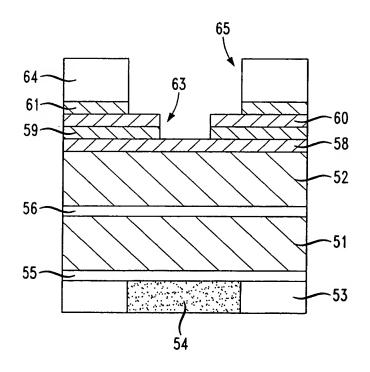


FIG. 18



a Semiconductor Device

FIG. 19

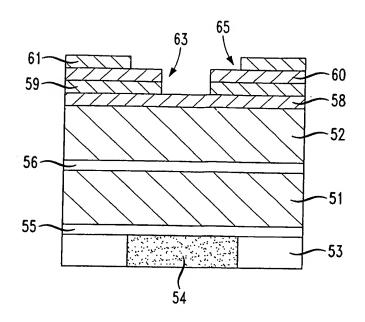
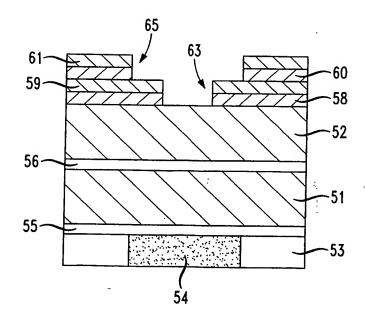


FIG. 20



HUANG 3-8-3-2-2-25-5
A Mask Layer and Interc act Structure for Dual Damascene Fab

3ct Structure for Dual Damascene Fabrication. a Semiconductor Device Robert L. Wolter (407-926-7700) Serial #10/026,257

FIG. 21

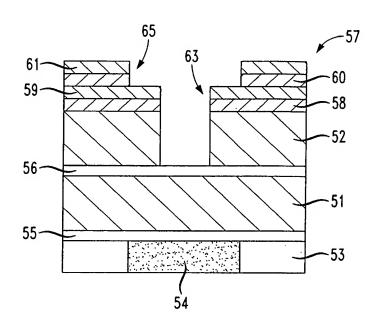
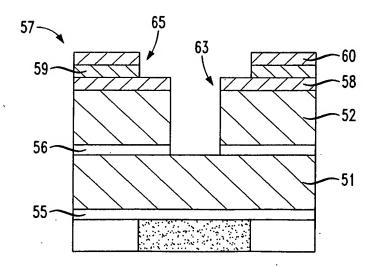


FIG. 22



HUANG 3-8-3-2-2-25-5

A Mask Layer and Interc. ct Structure for Dual Damascene Fabrication.
Robert L. Wolter (407-926-7700)
Serial #10/026,257

a Semiconductor Device

FIG. 23

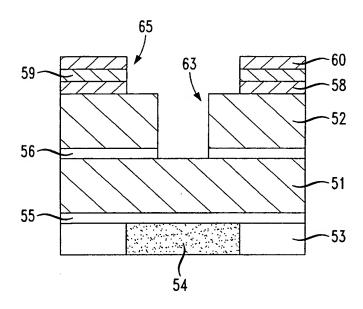
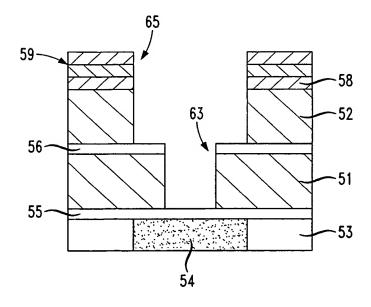


FIG. 24



HUANG 3-8-3-2-2-25-5
A Mask Layer and Interc set Structure for Dual Damascene Fa

3ct Structure for Dual Damascene Fabricatio. . a Semiconductor Device Robert L. Wolter (407-926-7700) Serial #10/026,257

FIG. 25

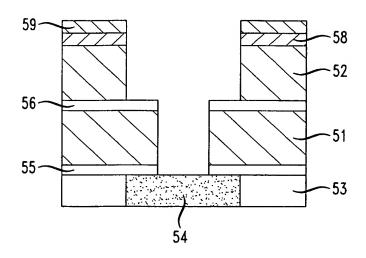
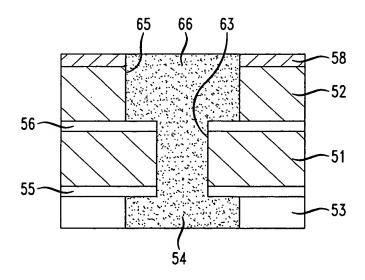


FIG. 26



HUANG 3-8-3-2-2-25-5 rect Structure for Dual Damascene Fabrication of a Semiconductor Device Robert L. Wolter (407-926-7700) Serial #10/026,257 A Mask Layer and Inter

FIG. 27

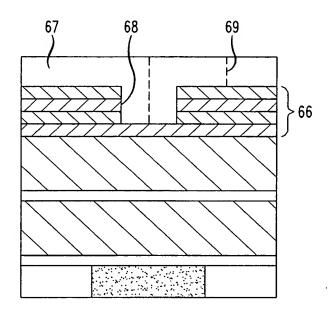
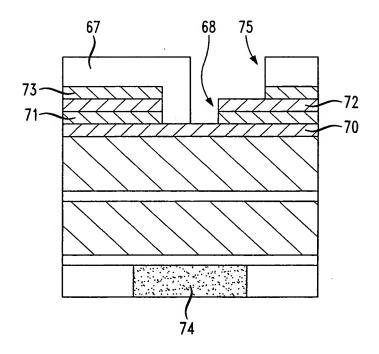


FIG. 28



A Mask Layer and Inte

HUANG 3-8-3-2-2-25-5
nect Structure for Dual Damascene Fabricat. of a Semiconductor Device
Robert L. Wolter (407-926-7700)
Serial #10/026,257

FIG. 29

